

Amendments to the Claims:

This listing of claims replaces all prior versions and listings of claims in the application:

Listing of Claims:

1. (original) A semiconductor device comprising:  
a semiconductor layer over an insulating surface;  
a gate insulating film on said semiconductor layer; and  
a gate electrode on said gate insulating film,  
wherein said semiconductor layer comprises a channel formation region, at least one LDD region in contact with said channel formation region, and a source region or a drain region in contact with said LDD region,  
wherein said gate electrode has a taper shape, and  
wherein said gate electrode comprises a laminate of a fourth electrode, a fifth electrode and a sixth electrode.

2. (currently amended) A semiconductor device comprising:  
a semiconductor layer over an insulating surface;  
a gate insulating film on said semiconductor layer; and  
a gate electrode on said gate insulating film,  
wherein said semiconductor layer comprises a channel formation region, at least one LDD region in contact with said channel formation region, and one of a source region and a drain region in contact with said LDD region,  
wherein said LDD region comprises a impurity region for giving one conductivity at a concentration of  $1 \times 10^{17}$  to  $1 \times 10^{20}$  atoms/cm<sup>3</sup>, and one of said source region and said drain region comprises said impurity element at a concentration of  $1 \times$  [[1020]]  $10^{20}$  to  $1 \times 10^{21}$  atoms/cm<sup>3</sup>,

wherein said gate electrode has a taper shape, and

wherein said gate electrode comprises a laminate of a fourth electrode, a fifth electrode and a sixth electrode.

3. (original) The semiconductor device as claimed in claim 1, wherein said fourth electrode is formed of a conductive film comprising tungsten or a material including tungsten as its main component, said fifth electrode is formed of a conductive film comprising aluminum or a material including aluminum as its main component, and said sixth electrode is formed of a conductive film comprising titanium or a material including titanium as its main component.

4. (original) The semiconductor device as claimed in claim 2, wherein said fourth electrode is formed of a conductive film comprising tungsten or a material including tungsten as its main component, said fifth electrode is formed of a conductive film comprising aluminum or a material including aluminum as its main component, and said sixth electrode is formed of a conductive film comprising titanium or a material including titanium as its main component.

5. (original) The semiconductor device as claimed in claim 1, said fourth electrode is overlapped with said LDD region through said gate insulating film.

6. (original) The semiconductor device as claimed in claim 2, said fourth electrode is overlapped with said LDD region through said gate insulating film.

7-24. (canceled)

25. (original) The semiconductor device as claimed in claim 1, wherein said semiconductor device is selected from the group consisting of a computer, a video camera, a digital camera, a mobile telephone, and a projector.

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26. (original) The semiconductor device as claimed in claim 2, wherein said semiconductor device is selected from the group consisting of a computer, a video camera, a digital camera, a mobile telephone, and a projector.